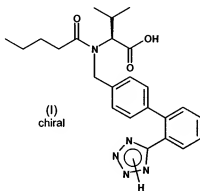


This listing of claims will replace all prior versions, and listings, of claims in the application.

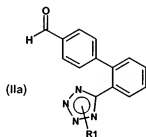
Listing of Claims:

Claim 1 (currently amended): A process for the manufacture of the compound of formula (I)

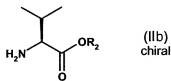


or a salt thereof, comprising

(a) reacting a compound of formula (II a)

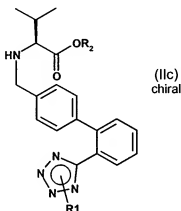


or a salt thereof, wherein R_1 is hydrogen or a tetrazole protecting group selected from the group consisting of tert-C₄-C₇-alkyl; C₁-C₂-alkyl that is mono- or disubstituted by phenyl, wherein the phenyl ring is un-substituted or substituted by one or more, residues selected from the group consisting of tert-C₁-C₇-alkyl, hydroxy, C₁-C₇-alkoxy, C₂-C₈-alkanoyl-oxy, halogen, nitro, cyano, and trifluoromethyl (CF₃); picolinyl; piperonyl; cumyl; allyl; cinnamoyl; fluorenyl; silyl; C₁-C₇-alkyl-sulphonyl; arylsulphonyl wherein the phenyl ring, when aryl is phenyl, is unsubstituted or substituted by one or more, residues selected from the group consisting of C₁-C₇-alkyl, hydroxy, C₁-C₇-alkoxy, C₂-C₈-alkanoyl-oxy, halogen, nitro, cyano, and CF₃; C₂-C₈-alkanoyl; and esterified carboxy, with a compound of formula

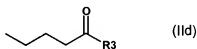


or a salt thereof, wherein R_2 represents hydrogen or a carboxy protecting group selected from the group consisting of C_1 - C_7 -alkyl; C_1 - C_2 -alkyl that is mono-, di or trisubstituted by phenyl, wherein the phenyl ring is un-substituted or substituted by one or more residues selected from the group consisting of C_1 - C_7 -alkyl, hydroxy, C_1 - C_7 -alkoxy, C_7 - C_8 -alkanoyl-oxy, halogen, nitro, cyano, and CF_3 ; picolinyl; piperonyl; allyl; cinnamyl; tetrahydrofuranlyl; tetrahydropyranlyl; methoxyethoxy-methyl, and benzyloxymethyl, under the conditions of a reductive amination; and

(b) acylating a resulting compound of formula (II c)

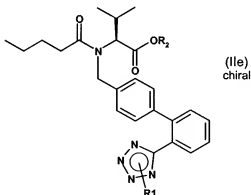


or a salt thereof with a compound of formula (II d)



wherein R_3 is an activating group; and,

(c) if R_1 and/or R_2 are different from hydrogen, removing the protecting group(s) in a resulting compound of formula (II e)



or a salt thereof; and

(d) isolating a resulting compound of formula (I) or a salt thereof; and, if desired, converting a resulting free acid of formula (I) into a salt thereof or converting a resulting salt of a compound

of formula (I) into the free acid of formula (I) or converting a resulting salt of a compound of formula (I) into a different salt.

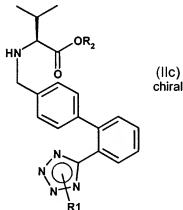
Claim 2 (original): The process according to claim 1, wherein in compounds of formulae (II a), (II b), (II c), and (II e) R_1 represents hydrogen and R_2 represents hydrogen and wherein in compounds of formula (II d) R_3 represents halogen.

Claim 3 (previous presented): The process according to claim 1, wherein the reductive amination is carried out in the presence of a reducing agent such as a borohydride, which may also be in complexed form, or hydrogen or a hydrogen donor both in the presence of a hydrogenation catalyst.

Claim 4 Canceled.

Claim 5 (previously presented): The process according to claim 1, wherein step (b) is carried out by first adding a compound of formula (II d) to a compound of formula (II c) and then slowly adding a sub-stoichiometric amount of a base in relation to the compound of formula (II d).

Claim 6 (currently amended): A process for the manufacture of a compound of formula



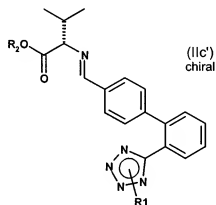
wherein R_1 represents hydrogen or a tetrazole protecting group selected from the group consisting of tert-C₄-C₇-alkyl; C₁-C₂-alkyl that is mono- or disubstituted by phenyl, wherein the phenyl ring is un-substituted or substituted by one or more, residues selected from the group consisting of tert-C₁-C₇-alkyl, hydroxy, C₁-C₇alkoxy, C₂-C₈-alkanoyl-oxy, halogen, nitro, cyano, and trifluoromethyl (CF₃); picolinyl; piperonyl; cumyl; allyl; cinnamoyl; fluorenyl; silyl; C₁-C₇-alkylsulphonyl; arylsulphonyl wherein the phenyl ring, when aryl is phenyl, is unsubstituted or substituted by one or more, residues selected from the group consisting of C₁-C₇-alkyl, hydroxy, C₁-C₇-alkoxy, C₂-C₈-alkanoyl-oxy, halogen, nitro, cyano, and CF₃; C₂-C₈-alkanoyl; and esterified carboxy, and R_2 represents hydrogen or a carboxy protecting group selected from the group

comprising reacting a compound of formula (II a)



wherein R₁ is hydrogen or a tetrazole protecting group selected from the group consisting of tert-C₄-C₇-alkyl; C₁-C₂-alkyl that is mono- or disubstituted by phenyl, wherein the phenyl ring is unsubstituted or substituted by one or more, residues selected from the group consisting of tert-C₁-C₇-alkyl, hydroxy, C₁-C₂-alkoxy, C₂-C₈-alkanoyl-oxy, halogen, nitro, cyano, and trifluoromethyl (CF₃); picolinyl; piperonyl; cumyl; allyl; cinnamoyl; fluorenyl; silyl; C₁-C₇-alkyl-sulphonyl; arylsulphonyl wherein the phenyl ring, when aryl is phenyl, is unsubstituted or substituted by one or more, residues selected from the group consisting of C₁-C₇-alkyl, hydroxy, C₁-C₇-alkoxy, C₂-C₈-alkanoyl-oxy, halogen, nitro, cyano, and CF₃; C₂-C₈-alkanoyl; and esterified carboxy, and R₂ is hydrogen or a carboxy protecting group selected from the group consisting of C₁-C₇-alkyl; C₁-C₂-alkyl that is mono-, di or trisubstituted by phenyl, wherein the phenyl ring is unsubstituted or substituted by one or more residues selected from the group consisting of C₁-C₇-alkyl, hydroxy, C₁-C₇-alkoxy, C₂-C₈-alkanoyl-oxy, halogen, nitro, cyano, and CF₃; picolinyl; piperonyl; allyl; cinnamyl; tetrahydrofuranlyl; tetrahydropyranylyl; methoxyethoxy-methyl, and benzyloxymethyl, excluding a compound of formula (II-c) wherein R₄ is ethyl and R₅ is trityl.

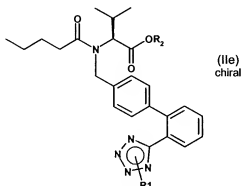
Claim 9 (currently amended): A compound of formula



wherein R₁ is hydrogen or a tetrazole protecting group selected from the group consisting of tert-C₄-C₇-alkyl; C₁-C₂-alkyl that is mono- or disubstituted by phenyl, wherein the phenyl ring is unsubstituted or substituted by one or more, residues selected from the group consisting of tert-C₁-C₇-alkyl, hydroxy, C₁-C₂-alkoxy, C₂-C₈-alkanoyl-oxy, halogen, nitro, cyano, and trifluoromethyl (CF₃); picolinyl; piperonyl; cumyl; allyl; cinnamoyl; fluorenyl; silyl; C₁-C₇-alkyl-sulphonyl; arylsulphonyl wherein the phenyl ring, when aryl is phenyl, is unsubstituted or substituted by one or more, residues selected from the group consisting of C₁-C₇-alkyl, hydroxy, C₁-C₇-alkoxy, C₂-C₈-alkanoyl-oxy, halogen, nitro, cyano, and CF₃; C₂-C₈-alkanoyl; and esterified carboxy, and R₂ is hydrogen or a carboxy protecting group selected from the group consisting of C₁-C₇-alkyl; C₁-C₂-alkyl that is mono-, di or trisubstituted by phenyl, wherein the phenyl ring is unsubstituted or substituted by one or more residues selected from the group consisting of C₁-C₇-alkyl, hydroxy,

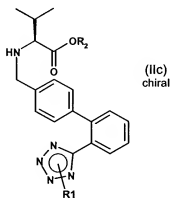
C₁-C₇-alkoxy, C₂-C₈-alkanoyl-oxy, halogen, nitro, cyano, and CF₃; picolinyl; piperonyl; allyl; cinnamyl; tetrahydrofuranlyl; tetrahydropyranylyl; methoxyethoxy-methyl, and benzyloxymethyl.

Claim 10 (currently amended): A process for the manufacture of a compound of formula

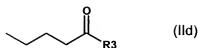


wherein R₁ represents hydrogen or a tetrazole protecting group selected from the group consisting of tert-C₄-C₇-alkyl; C₁-C₂-alkyl that is mono- or disubstituted by phenyl, wherein the phenyl ring is un-substituted or substituted by one or more, residues selected from the group consisting of tert-C₁-C₇-alkyl, hydroxy, C₁-C₂-alkoxy, C₂-C₈-alkanoyl-oxy, halogen, nitro, cyano, and trifluoromethyl (CF₃); picolinyl; piperonyl; cumyl; allyl; cinnamoyl; fluorenyl; silyl; C₁-C₇-alkyl-sulphonyl; arylsulphonyl wherein the phenyl ring, when aryl is phenyl, is unsubstituted or substituted by one or more, residues selected from the group consisting of C₁-C₇-alkyl, hydroxy, C₁-C₇-alkoxy, C₂-C₈-alkanoyl-oxy, halogen, nitro, cyano, and CF₃; C₂-C₈-alkanoyl; and esterified carboxy, and R₂ represents hydrogen or a carboxy protecting group selected from the group consisting of C₁-C₇-alkyl; C₁-C₂-alkyl that is mono-, di or trisubstituted by phenyl, wherein the phenyl ring is un-substituted or substituted by one or more residues selected from the group consisting of C₁-C₇-alkyl, hydroxy, C₁-C₇-alkoxy, C₂-C₈-alkanoyl-oxy, halogen, nitro, cyano, and CF₃; picolinyl; piperonyl; allyl; cinnamyl; tetrahydrofuranlyl; tetrahydropyranylyl; methoxyethoxy-methyl, and benzyloxymethyl,

comprising acylating a resulting compound of formula (II c)



or a salt thereof with a compound of formula (II d)



wherein R₃ is an activating group.

Claim 11 (previously presented): The process according to claim 2, wherein the reductive amination is carried out in the presence of a reducing agent such as a borohydride, which may also be in complexed form, or hydrogen or a hydrogen donor both in the presence of a hydrogenation catalyst.

Claim 12 Canceled.

Claim 13 (previously presented): The process according to claim 2, wherein step (b) is carried out by first adding a compound of formula (II d) to a compound of formula (II c) and then slowly adding a sub-stoichiometric amount of a base in relation to the compound of formula (II d).

Claim 14 (new): A compound of formula (IIc) according to claim 8 selected from the group consisting of:

(S)-3-Methyl-2-((2'-(1H-tetrazol-5-yl)-biphenyl-4-ylmethyl)-amino)-butyric acid,
(S)-3-Methyl-2-([2'-(1H-tetrazol-5-yl)-biphenyl-4-yl-methyl]-amino)-butyric acid benzylester, (S)-3-Methyl-2-((2'-(1H-tetrazol-5-yl)-biphenyl-4-yl-methyl)-amino)-butyric acid tert-butylester,
(S)-2-((2'-(2"-tert-Butyl-tetrazol-5"-yl)-biphenyl-4-ylmethyl)-amino)-3-methyl-butylric acid,
(S)-2-([2'-(2-Benzyl-2H-tetrazol-5-yl)-biphenyl-4-ylmethyl]-amino)-3-methyl-butylric acid benzyl ester, and
(S)-2-([2'-(2-tert-Butyl-2H-tetrazol-5-yl)-biphenyl-4-ylmethyl]-amino)-3-methyl-butylric acid tert-butyl ester.

Claim 15 (new): The compound of formula (IIc') according to claim 9 which is 3-methyl-2-[1-[2'-(1H-tetrazol-5-yl)-biphenyl-4-yl]-meth-(E/Z)-ylidene]-amino)-butyric acid.